



ACT Node Standard Recipes

Resist	ma-N 2405		Sample Prep for Resist spin	
Tone	Negative Tone Resist	Cleaning Solution	Sonicate	
Solid content		Acetone	2~5 min	
Developer	ma-D 532	IPA	2~5 min	
Stopper	ISO-Propanol	Ethanol (optional)	2~5 min	
Remover	Acetone	DI Water Rinse	2~5 min	
Thinner	mr-T 1090	Bake	5 min 30 min	
Adhesion Promoter	HMDS / SurPass 4000 – Required for Si and SiO2 samples	Hotplate-100°C Oven(optional) - 200°C		

Spin	Speed	Thickness	Time
	3000rpm		30 s
Pre-Bake	90 °C	if Hot Plate used	90 s
	180 °C	if oven used	30 min
Exposure	Voltage	Base Dose	
	20kV	170 ~ 250 (uC/cm2)	
Develop	ma-D 532		45 s - 1 min
Rinse	DI water	De-Ionised Water	5- 10 min N2 Blow
Post Bake before etch (if required)	100 °C		5 ~15 min
Remover	Acetone	Time depends on the patterns and thickness of resist to be removed.	Soak for 30 ~ 40 mins
		DI Water rinse	1 min

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